

## **Amendments to the Specification**

Please amend the paragraph beginning on line 2 of page 9 as follows:

Exemplary precursor and/or purge gas inlets 22 and 24 are shown diagrammatically for emitting precursor and/or purge gases to within chamber 12 intermediate substrate 14 and surface plane antenna 18. A vacuum draw-down line 26 is diagrammatically shown for exhausting material from ~~chamber 26~~ chamber 12. The Fig. 1 apparatus is diagrammatic and exemplary in construction only, with any other suitable apparatus being usable in accordance with the methodical aspects of the invention. For example, any alternate configuration, such as showerheads, multiple ports or other means, whether existing or yet-to-be developed, are also of course contemplated for getting gas to the chamber and exhausting material from the chamber.

Please amend the paragraph beginning on line 6 of page 12 as follows:

Also in any of the above-described and subsequent embodiments, the first precursor gas flowing can be with or without plasma within the chamber, for example with ~~or~~ or without surface microwave plasma generation within the chamber with the first precursor gas flowing. Further, remote plasma generation could also be utilized with the first precursor gas flowing, and also with the second precursor gas flowing in combination with surface microwave plasma conditions within the chamber during the second precursor gas flowing.

Please amend the paragraph beginning on line 9 of page 19 as follows:

After forming the second monolayer, another inert purge gas flowing P4 (the same or different in composition in some way to that of the first ~~precursor~~ purge gas) is begun prior to commencing a reducing of the plasma capable power. For example, Fig. 5 depicts the P4 pulse commencing at a time point 46 which is before a time point 48 when a reducing from the plasma capable power starts to occur.